

# 제23회 한국반도체학술대회

2016년 2월 22일(월)-24일(수), 강원도 하이원리조트

## J. Nano-Science & Technology 분과

Room H  
육백 I (6층)

2016년 2월 23일(화) 15:10-17:10

[TH3-J] Graphene and Related Carbon Nanostructures

좌장 : Steve Park(KAIST), 황동목(성균관대학교)

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| TH3-J-1 | 15:10-15:40 | <b>[초청] Catalytic Growth of 2D Carbon Monolayer with Controlled Crystallinity: from Amorphous to Single-crystal</b><br>Dongmok Whang<br><i>School of Advanced Materials Science and Engineering, SKKU<br/>Advanced Institute of Nanotechnology, Sungkyunkwan University</i>                                                                                                                                                                                                                                                                                                                                                                                                                                                                                  |
| TH3-J-2 | 15:40-15:55 | <b>Origin of High-energy Kinks in the <math>\sigma</math> Bands of Graphene</b><br>Sung Won Jung <sup>1,2</sup> , Jimin Kim <sup>1,2</sup> , Woo Jong Shin <sup>1,2</sup> , and Keun Su Kim <sup>1,2</sup><br><i><sup>1</sup>Center for Artificial Low Dimensional Electronic Systems, Institute for<br/>Basic Science, <sup>2</sup>Department of Physics, Pohang University of Science<br/>and Technology</i>                                                                                                                                                                                                                                                                                                                                               |
| TH3-J-3 | 15:55-16:10 | <b>Stretchable, Transparent and Ultrasensitive Strain Sensor based on Carbon Nanotube for Human-Machine Interface</b><br>Eun Roh, Byeong Ung Hwang, Doil Kim, Bo-Yeong Kim, and Nae-Eung Lee<br><i>SKKU Advanced Institute of Nanotechnology, Sungkyunkwan<br/>University</i>                                                                                                                                                                                                                                                                                                                                                                                                                                                                                |
| TH3-J-4 | 16:10-16:25 | <b>Atomic Layer Deposition of Ultrathin Metal Oxide Films on Graphene Incorporated Device in a Wafer Scale</b><br>Seong-Jun Jeong <sup>1</sup> , Jinseong Heo <sup>1</sup> , Hyowon Kim <sup>1</sup> , Yeahyun Gu <sup>2</sup> ,<br>Jaehyun Yang <sup>2</sup> , Hyoungsub Kim <sup>2</sup> , Min-Hyun Lee <sup>1</sup> , Hyun Jae Song <sup>1</sup> ,<br>Chang-Seok Lee <sup>1</sup> , Jiyeon Ku <sup>1</sup> , Yunseong Lee <sup>1</sup> , Yeonchoo Cho <sup>1</sup> , Woojin<br>Jeon <sup>1</sup> , Sungwoo Hwang <sup>1</sup> , and Seongjun Park <sup>1</sup><br><i><sup>1</sup>Device Laboratory, DS Center, Samsung Advanced Institute of<br/>Technology, <sup>2</sup>Department of Materials Science and Engineering,<br/>Sungkyunkwan University</i> |
| TH3-J-5 | 16:25-16:40 | <b>Graphene/High-<math>\kappa</math>/p-Si Junctions: A Theoretical and Experimental Study</b><br>Jaewoo Shim and Jin-Hong Park<br><i>School of Electronics and Electrical Engineering, Sungkyunkwan<br/>University</i>                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                       |
| TH3-J-6 | 16:40-16:55 | <b>Atomic Layer Etching of a MoS<sub>2</sub> Film</b><br>Kihyun Kim <sup>1</sup> , Kiseok Kim <sup>1</sup> , Kyongnam Kim <sup>1</sup> , and Geunyoung Yeom <sup>1,2</sup><br><i><sup>1</sup>Department of Advanced Materials Science and Engineering,<br/>Sungkyunkwan University, <sup>2</sup>SKKU Advanced Institute of Nano</i>                                                                                                                                                                                                                                                                                                                                                                                                                          |

The 23<sup>rd</sup> Korean Conference on Semiconductors (KCS 2016)

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*Technology (SAINT), Sungkyunkwan University*

**TH3-J-7      16:55-17:10      Atomic Layer Deposition of Mesocrystalline Hf-Al-O Thin Film by using Phase Transition Engineering for High Performance Metal Oxide Graphene Field-Effect-Transistor**  
Yunseong Lee, Woojin Jeon, Min-Hyun Lee, Sanghyun Jo, Seongjun Park, and Seong-Jun Jeong  
*Device Laboratory, Device and System Center, Samsung Advanced Institute of Technology*